Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S38 5	36	mask.clm. and (alignment adj mark).clm. and ((fill or filled or filling or bury or burying or buried) near10 (hole or via or opening) near10 metal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 16:13
S38 6	19	mask.clm. with (alignment adj mark).clm. and ((fill or filled or filling or bury or burying or buried) near10 (hole or via or opening) near10 metal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 16:13
S38 7	18	mask.clm. near10 (alignment adj mark).clm. and ((fill or filled or filling or bury or burying or buried) near10 (hole or via or opening) near10 metal)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 16:14
S38 · 8	9	mask.clm. near10 (alignment adj mark).clm. and ((fill or filled or filling or bury or burying or buried) near10 (hole or via or opening) near10 metal) and mask.ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2005/12/11 16:15
S38 9	5	mask.clm. near10 (alignment adj mark).clm. and ((fill or filled or filling or bury or burying or buried) near10 (hole or via or opening) near10 metal) and mask.ab. and (metal near10 (gold or platinum or silver or aluminum))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 16:16
S39 0	8	mask.clm. near10 (alignment adj mark).clm. and ((fill or filled or filling or bury or burying or buried) near10 (hole or via or opening) near10 metal) and mask.ab. and (metal near10 (copper or tungsten or gold or platinum or silver or aluminum))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 16:16
S39 1	1703	(method same mask same (alignment adj mark))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:52
S39 2	100	(method same mask same (alignment adj mark) same (simultaneously or simultaneous or ((one) adj time)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:53

S39 3	13	(method same mask same (alignment adj mark) same (simultaneously or simultaneous or ((one) adj time))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/04/05 15:54
S39 4	1	(method same mask same ((first or second) adj (alignment adj mark)) same (simultaneously or simultaneous or ((one) adj time))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:55
S39 5	3	(method same mask same ((first or second) adj (alignment adj mark)) same (simultaneously or simultaneous or ((one) adj time)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:56
S39 6	1	10/080104	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:55
S39 7	14	(method same mask same ((first or second) adj (alignment adj mark)) same (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:56
S39 8	11	(method with mask same ((first or second) adj (alignment adj mark)) same (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:56
S39 9	9	(method with mask with ((first or second) adj (alignment adj mark)) same (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:57
S40 0	8	(method with mask with ((first or second) adj (alignment adj mark)) with (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/04/05 15:57
S40 1	7	(method with mask with ((form or forming or formed or formation)) with ((first or second) adj (alignment adj mark)) with (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/04/05 16:17

S40 2	3	(method with mask with ((form or forming or formed or formation)) with ((first or second) adj (alignment adj mark)) with (simultaneously or simultaneous or time)) and (method or process).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:58
S40 3	11	(mask with ((form or forming or formed or formation)) with ((first or second) adj (alignment adj mark)) with (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 16:18
S40 4	. 4	(mask with ((form or forming or formed or formation)) with ((first or second) adj (alignment adj mark)) with (simultaneously or simultaneous or time)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 16:18
S40 5	11	(mask with ((form or forming or formed or formation)) with ((first or second) adj (alignment adj mark)) with (simultaneously or simultaneous or time))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 12:46
S40 7	50	(mask same (first adj alignment adj mark) same (second adj alignment adj mark)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 12:53
S40 8	153	(mask same (first adj alignment adj mark) same (second adj alignment adj mark))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 13:57
S40 9	50	(mask same (first adj alignment adj mark) same (second adj alignment adj mark)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 13:57
S41 0	48	(mask with (first adj alignment adj mark) same (second adj alignment adj mark)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 13:57
S41 1	48	(mask with (first adj alignment adj mark) with (second adj alignment adj mark)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 13:58

S41 2	43	(mask near10 (first adj alignment adj mark) with (second adj alignment adj mark)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 13:58
S41 3	40.	(mask near10 (first adj alignment adj mark) near10 (second adj alignment adj mark)).clm:	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 14:03
S41 4	25	((mask near10 (first adj alignment adj mark) near10 (second adj alignment adj mark)) same pattern).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 14:03
S41 5	11	((mask near10 (first adj alignment adj mark) near10 (second adj alignment adj mark)) same pattern same exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 14:07
S41 6	6	((method or process) same (mask near10 (first adj alignment adj mark) near10 (second adj alignment adj mark)) same pattern same exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 14:08
S41 7	7	((method or process) same (mask near10 (first adj alignment adj mark) same (second adj alignment adj mark)) same pattern same exposure).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 14:22
S41 8	2	((method or process) same (mask near10 (first adj alignment adj mark) same (second adj alignment adj mark)) same pattern same exposure same (time or sequential or sequentially or simultaneous or simultaneously)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 14:23
S41 9	3	((mask near10 (first adj alignment adj mark) same (second adj alignment adj mark)) same pattern same exposure same (time or sequential or sequentially or simultaneous or simultaneously)). clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/07 14:19